Materials List for:

Developing High Performance GaP/Si Heterojunction Solar Cells

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URL: https://www.jove.com/video/58292
DOI: doi:10.3791/58292

Materials

Name	Company	Catalog Number	Comments
Hydrogen peroxide, 30%	Honeywell	10181019	
Sulfuric acid, 96%	KMG electronic chemicals, Inc.	64103	
Hydrochloric acid, 37%	KMG electronic chemicals, Inc.	64009	
Buffered Oxide Etch 10:1	KMG electronic chemicals, Inc.	62060	
Hydrofluoric acid, 49%	Honeywell	10181736	
Acetic acid	Honeywell	10180830	
Nitride acid, 69.5%	KMG electronic chemicals, Inc.	200288	

